L Number	Hits	Search Text	DB	Time stamp
1	2492	(exposure adj apparatus) and lithography	USPAT;	2004/02/18 16:28
			US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
2	1852	((exposure adj apparatus) and lithography) and stage	USPAT;	2004/02/18 16:29
			US-PGPUB;	, -
- 1	'		EPO; JPO;	
			IBM_TDB	
3	1783	(((exposure adj apparatus) and lithography) and stage) and	USPAT;	2004/02/18 16:29
		(mask or reticle)	US-PGPUB;	
			EPO; JPO;	,
1			IBM_TDB	
4	2134	((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
		table)	US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
5	2020	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
		table)) and (mask or reticle)	US-PGPUB;	
			EPO; JPO;	
1_			IBM_TDB	2004/02/40 46:20
6	1362	((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:30
		table)) and (mask or reticle)) and illumination	US-PGPUB;	
			EPO; JPO;	
	1040	At a constant of the second of	IBM_TDB	2004/02/10 16:21
7	1342	(((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:31
		table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	
]		specimen or sample)	EPO; JPO; IBM_TDB	
	170	/////overacture adj apparatus) and lithography) and (ctage or	USPAT;	2004/02/18 16:32
8	170	((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	2004/02/16 10.32
		specimen or sample)) and (reaction near4 force)	EPO; JPO;	
		speciment of sample), and (reaction heart force)	IBM_TDB	
9	206	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:32
	200	table)) and (reaction near4 force)	US-PGPUB;	2001,02,1010.02
		able // and (redection from the follow)	EPO; JPO;	
	•		IBM_TDB	
10	118	(((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:32
	-	or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic	IBM_TDB	
11	100	((((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:33
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet	IBM_TDB	
12	56	((((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:34
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
	= -	electromagnetic) and magnet) and (driver or mover)	IBM_TDB	2004/02/40 46 24
13	24	(((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/02/18 16:34
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover))	IBM_TDB	
14	_	and stator	LICDAT	2004/02/19 16:49
14	9	((((((((((((((((((((((((((((((((((((((USPAT;	2004/02/18 16:48
		(stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force))	US-PGPUB; EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover)	IBM_TDB	
		and stator) and (magnetic adj pole)	10.1_100	!
		and season, and (magnetic adj pole)	L	